



1755
PATENT APPLICATION
Do. No. 1941-70

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of: Paul J. BRUINSMA, Suresh BASKARAN, Jagannadha R. BONTHA
and Jun LIU

Serial No. 09/481,988

Examiner: P. Marcantoni

Filed: January 11, 2000

Group Art Unit: 1755

For: MESOPOROUS-SILICA FILMS, FIBERS, AND POWDERS BY EVAPORATION

Date: November 13, 2000

Box FEE AMENDMENT
Assistant Commissioner for Patents
Washington, D.C. 20231

Responsive to the Office Action dated August 10, 2000, enclosed is an amendment in the above-identified application.

The fee has been calculated as shown below.

<u>CLAIMS AS AMENDED</u>					
For:	Number After Amendment	Previous Number	Extra	Rate	Additional Fee
Total Claims	75	-71	4	x \$ 9 =	\$36
Independent Claims	14	-12	2	x \$39 =	\$78
TOTAL ADDITIONAL FEE FOR THIS AMENDMENT					\$114

The Commissioner is hereby authorized to charge deposit account number 13-1703 the amount of \$114.

Respectfully submitted,

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RESPONSE TO OFFICE ACTION

Responsive to the Office Action, dated August 10, 2000, please amend the application as follows.

*New matter?
looks like it*

IN THE CLAIMS

Please amend claims 32, 53, 55, 58 and 62 as follows:

32. (Amended) A process to form mesostructured films, comprising:

(a) preparing a precursor sol containing a soluble source of a metal oxide, water, an organic solvent, surfactant and acid or base catalyst, wherein the surfactant concentration c_0 [is much less than] does not exceed the critical micelle concentration and the surfactant is present as free surfactant; and

(b) depositing the precursor sol on a substrate wherein evaporation of solvent and water causes the formation of said mesostructured films on the substrate surface wherein said mesostructured films are identified by XRD peaks in the range 20-2°-6° hexagonal, cubic, or lamellar electron diffraction patterns.

33. (Amended) The method of claim 42 wherein the mesoporous film has a refractive index [of less than] as low as approximately 1.16.

RESPONSE TO OFFICE ACTION

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*ok no longer new matter
see col. 10 lines 10-11*

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